	ŭ	Document ID	Issue Date Pages	Pages	Title	Current OR	Current XRef	Inventor	cor
1	US	US 6242306 Bl	20010605	6	Dual bit isolation scheme for flash memory devices having polysilicon floating gates	438/262	438/257	Pham, Tuan et al.	e t
7	ns	5414693 A	19950509	11	Self-aligned dual-bit split gate (DSG) flash EEPROM cell	365/185.1	257/315; 257/316	Ma, Yueh Y. al.	í. et
m	US	5021999 A	19910604	15	Non-volatile semiconductor memory device with facility of storing tri-level data	365/185.03	257/316; 365/104; 365/185.1; 365/185.11; 365/185.11; 365/185.32; 365/189.01; 365/230.06	Kohda, Kenji et al.	ıji et
4	us	6366500 Bl	20020402	22	Process for making and programming and operating a dual-bit multi-level ballistic flash memory		365/185.14	Ogura, Seiki al.	ki et
2	us	6248633 Bl		23	Process for making and programming and operating a dual-bit multi-level ballistic MONOS memory		438/287	Ogura, Seiki al.	ki et
9	US	US 6133098 A	20001017	23	Process for making and programming and operating a dual-bit multi-level ballistic flash memory	438/267		Ogura, Seiki et al.	ki et